

EAST Search History

EAST Search History (Prior Art)

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	2	"20020106891"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2009/07/20 15:39
S1	0	10/702049	USPAT	OR	OFF	2007/09/17 16:19
S2	2	10/702049	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/18 12:50
S4	72	"6316167"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/18 17:08
S5	7252	((430/313/) or (430/272.1/) or (430/311/) or (427/569/) or (427/282/) or (427/535/)). OCLS.	USPAT; USOCR	OR	OFF	2007/09/18 17:09
S7	3	S5 and TERA	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/18 17:11
S8	1666	S5 and deposit	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/18 17:11
S9	0	S5 and deposit and etch and R:C:H:X	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/18 17:12
S10	0	S5 and deposit and R:C:H:X	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/18 17:12
S11	0	S5 and deposit and R:C:O:X	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/18 17:12

S12	2	S5 and R:C.O:X	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/18 17:13
S13	2	S5 and RCHX	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/18 17:14
S14	37	RCHX	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/18 17:14
S15	5	RCHX and deposit	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/18 17:14
S16	0	RCHX and deposit and HZ	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/18 19:09
S17	5	RCHX and deposit	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/18 17:16
S18	2	"20040178169"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/21 21:18
S19	0	RCHX and HZ and watt	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/18 19:09
S20	2	RCHX and HZ	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/18 19:10
S21	4	"6903023"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/18 19:12

S22	2	"20070037100"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/18 19:15
S23	2	"20060049139"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/18 19:16
S24	2	"20040000534"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/18 19:26
S25	4	"1905170"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/18 19:27
S26	0	"19901905170"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/18 19:27
S27	121	"4905170"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/18 19:28
S28	82	"4905170"	USPAT; USOCR	OR	OFF	2007/09/19 12:31
S29	1	2002/0076843	USPAT; USOCR	OR	OFF	2007/09/19 12:32
S30	1	2002/0076843	USPAT; USOCR	OR	OFF	2007/09/19 12:33
S31	6	"6287959"	USPAT; USOCR	OR	OFF	2007/09/19 12:36
S32	20	"6380611"	USPAT; USOCR	OR	OFF	2007/09/19 12:41
S33	439343	(ARC or (anti near reflect\$3 near coat\$4)) deposit and rate and time	USPAT; USOCR	OR	OFF	2007/09/19 12:43
S34	110	(ARC or (anti near reflect\$3 near coat\$4)) with deposit with rate	USPAT; USOCR	OR	OFF	2007/09/19 12:44
S35	1	(anti near reflect\$3 near coat\$4) with deposit with rate	USPAT; USOCR	OR	OFF	2007/09/19 12:47
S36	8249	tetramethylcyclotetrasilicate or tetraethylorthosilicate or dimethyldimetoxy silane or octamethylcyclotetrasiloxane	USPAT; USOCR	OR	OFF	2007/09/19 12:50

S37	13879	tetramethylcyclotetrasilicate or tetraethylorthosilicate or dimethyldimetoxy silane or octamethylcyclotetrasiloxane	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/19 13:20
S38	1405	S37 and deposit and etch	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/19 12:52
S39	0	"I0" and (deposit near ratea)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/19 12:52
S40	0	"I0" and (deposit near rate)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/19 12:52
S41	0	"I0" and (deposit near rate)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/19 12:52
S42	1	"I10" and (deposit near rate)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/19 12:53
S43	95	"I10" and ((inert near gas) or nitrogen or argon)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/19 12:54
S44	2	"10662022"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/19 13:11
S45	4	"7030468"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/19 13:21
S46	2	"10377061"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/19 17:09

S47	1	11/023815	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/19 17:10
S48	1	11/023815	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/19 17:10
S49	4	"7097779"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/21 21:26
S50	0	"SiCOH" with etch with "DC" with bias	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/21 21:27
S51	1	"RCHX" with etch with "DC" with bias	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/24 17:44
S52	1	11/801058	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/24 17:45
S53	50	"6316167"	USPAT	OR	OFF	2007/10/03 15:21
S54	50	"6316167"	USPAT	OR	OFF	2007/10/03 15:23
S55	53	etch and SiCH and hydrogen	USPAT	OR	OFF	2007/10/03 15:23
S56	166	etch and SiCH and hydrogen	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/03 15:23
S57	202	etch with SiCH with hydrogen	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/03 15:23
S58	0	etch with SiCH with hydrogen	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/03 15:23

S59	6	etch same SiCH same hydrogen	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/03 15:25
S60	0	etch same SiCH same hydrogen and sccm	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/03 15:25
S61	6	etch same SiCH same hydrogen and rate	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/03 15:27
S62	6	"7183201"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/03 15:30
S63	4	09/912103	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/03 15:30
S64	1	"7030008"	USPAT	OR	OFF	2007/10/04 10:24
S65	0	"20050100683"	USPAT	OR	OFF	2007/10/04 10:25
S66	1	"20050100683"	US-PGPUB; USPAT	OR	OFF	2007/10/04 11:09
S67	45	"6063233"	US-PGPUB; USPAT	OR	OFF	2007/10/04 11:34
S68	17	plasma and deposition and SiCOH and shower and temperature	US-PGPUB; USPAT	OR	OFF	2007/10/04 11:35
S69	17	plasma and deposition and SiCOH and shower and temperature	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/04 11:35
S70	18	plasma and deposit\$4 and SiCOH and shower and temperature	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/04 11:36
S71	6	plasma and deposit\$4 and SiCOH and (shower with temperature)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/04 11:46

S72	0	(plasma with deposit\$4 with SiCOH)and (post near process)and ((de near chuck) or remove or lift)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/04 11:47
S73	0	(plasma same deposit\$4 same SiCOH)and (post near process)and ((de near chuck) or remove or lift)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/04 11:48
S74	4	(plasma and deposit\$4 and SiCOH)and (post near process)and ((de near chuck) or remove or lift)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/04 12:16
S75	15	plasma and deposit\$4 and (TERA or SiCOH or organosilicate)and(post near process)and ((de near chuck) or remove or lift)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/04 12:26
S76	15	plasma and deposit\$4 and (TERA or SiCOH or SiCNH or organosilicate)and(post near process)and((de near chuck) or remove or lift)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/04 12:30
S77	7	2002-194431	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/04 12:35
S78	24	"6380611"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/04 12:36
S79	7	"6287959"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/04 12:39
S80	2	"20020076843"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/04 12:45
S81	57	SiCOH and deposit and plasma and (tetramethylcyclotetrasilane or tetraethylorthosilicate or dimethyldimethoxysilane or octamethylcyclotetrasiloxane)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/04 12:47

S82	24	SICOHwith deposit with plasma with (tetramethylcyclotetrasilane or tetraethylorthosilicate or dimethyldimethoxysilane or octamethylcyclotetrasiloxane)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/04 13:06
S83	0	SICOH with deposit with plasma with (tetramethylcyclotetrasilane or tetraethylorthosilicate or dimethyldimethoxysilane or octamethylcyclotetrasiloxane)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/04 13:06
S84	0	SICOH same deposit same plasma same (tetramethylcyclotetrasilane or tetraethylorthosilicate or dimethyldimethoxysilane or octamethylcyclotetrasiloxane)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/04 13:06
S85	0	SICOH same deposit same plasma same (tetramethylcyclotetrasilane or tetraethylorthosilicate or dimethyldimethoxysilane or octamethylcyclotetrasiloxane)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/04 13:06
S86	57	SICOH and deposit and plasma and (tetramethylcyclotetrasilane or tetraethylorthosilicate or dimethyldimethoxysilane or octamethylcyclotetrasiloxane)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/04 13:07
S87	75	(SICOH with deposit\$4) and plasma and (tetramethylcyclotetrasilane or tetraethylorthosilicate or dimethyldimethoxysilane or octamethylcyclotetrasiloxane)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/04 13:22
S88	72	"6316167"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/13 02:47
S89	3	"20030017694"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/13 03:08
S90	72	"6316167"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/13 03:40
S91	33	"6436808"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/13 03:40

S92	2	deposit and chamber and (SiCOH)and (shower with temperature)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/13 03:46
S93	19466105	US "6764951" B1	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/13 03:44
S94	4	"6764951"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/13 03:45
S95	6	(SiCOH)and (shower with temperature)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/13 05:36
S96	5	(SiOH)and (shower with temperature)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/13 03:51
S97	6	organosilicon and (shower with temperature)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/13 03:52
S98	19	"885985"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/13 04:26
S99	2	"20030003768"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/13 04:26
S100	2	("SiCOH" or organosilicate)and (shower with temperature)and deposit	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/13 05:37
S101	2	("SiCOH" or organosilicate)and (shower with temperature)and deposit	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/13 06:17

S102	16	"638803"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/13 05:40
S103	21	("SiCOH" or organosilicate)and (wall with temperature)and deposit	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/13 05:53
S104	9	"938435"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/13 05:53
S105	2	("SiCOH" or organosilicate)and (shower with (temperature or centigrade))and deposit	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/13 06:24
S106	16	"638803"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/13 06:22
S107	331	(shower with (temperature or centigrade)) and deposit	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/13 06:24
S108	180	(shower with (temperature or centigrade)) and deposit and uniform	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/13 06:24
S109	3	(shower with (temperature or centigrade)) with deposit with uniform	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/13 06:28
S110	21	(shower with (temperature or centigrade)) with deposit	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/13 06:43
S111	0	((de near chuck\$3) with substrate or wafer)with while with plasma	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/13 06:47

S112	0	((de near chuck\$3) with substrate or wafer)with while with deposit	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/13 06:47
S113	0	((de near chuck\$3) with substrate or wafer)same while same deposit	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/13 06:47
S114	0	((de near chuck\$3) same substrate or wafer)same while same deposit	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/13 06:47
S115	0	(de near chuck\$3) and (substrate or wafer) and while and deposit	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/13 06:48
S116	0	((de near chuck\$3)with (substrate or wafer)))and while and deposit	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/13 06:53
S117	77	((de near chuck\$3)with (substrate or wafer))) and deposit	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/13 07:00
S118	1	((de adj chuck\$3)with (substrate or wafer))) with deposit	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/13 07:00
S119	1	((de adj chuck\$3)with (substrate or wafer))) same deposit	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/13 07:00
S120	1	((de adj chuck\$3)same (substrate or wafer))) same deposit	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/13 07:00
S121	77	((de adj chuck\$3)same (substrate or wafer))) and deposit	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/13 07:01

S122	76	(((de adj chuck\$3) same (substrate or wafer))) and deposit and (during or while or after or before)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/13 07:12
S123	5440	(((lift\$3) with (substrate or wafer))) and deposit and (during or while or after or before)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/13 07:12
S124	71	(((lift\$3) with (substrate or wafer))) with deposit with (during or while or after or before)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/13 07:13
S125	71	(((lift\$3) with (substrate or wafer))) with deposit with (during or while or after or before)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/13 07:13
S126	2	"5466524"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/15 18:42
S127	1	"10546736"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/15 18:43
S128	1	"10546736"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/15 18:44
S129	1	10/534401	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/15 18:44
S130	64	plasma and (de near chuck)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/24 19:17
S131	6	"6452775"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/25 11:25

S132	0	(de near chuck) and (plasma near deposit \$4)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/25 11:25
S133	1	(de near chuck) and (plasma near deposit \$4)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/25 11:28
S134	39	(de near chuck) and (plasma with deposit \$4)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/25 11:28
S135	2	"20050100683"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/25 11:57
S136	2	"20050100683"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/25 11:58
S137	1	((de near chuck or " de-chuck") with (plasma near(coat\$4 or deposit)))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/25 12:00
S138	1	((de near chuck or " de-chuck") same (plasma near(coat\$4 or deposit)))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/25 12:00
S139	1	((de near chuck or " de-chuck") and (plasma near(coat\$4 or deposit)))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/25 12:00
S140	25	((de near chuck or " de-chuck") and (plasma same(coat\$4 or deposit)))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/25 13:40
S141	6	"2006004506"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/25 13:29

S142	13	"931272"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/25 13:29
S143	64	(de near chuck or " de-chuck") and plasma	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/25 14:26
S144	2	"20040137169"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/25 14:33
S145	0	((before with (substrate or wafer)) with lift) and palsma	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/25 14:34
S146	0	((before same (substrate or wafer)) with lift) and palsma	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/25 14:34
S147	0	((before same (substrate or wafer)) with lift\$4) and palsma	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/25 14:34
S148	0	((before same (substrate or wafer)) same lift\$4) and palsma	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/25 14:35
S149	2940	((before same (substrate or wafer)) same lift\$4)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/25 14:35
S150	957	((before same (substrate or wafer)) same lift\$4)and plasma	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/25 14:35
S151	2940	((before same (substrate or wafer)) same lift\$4)sameplasma	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/25 14:35

S152	223	((before same (substrate or wafer)) same lift\$4)same plasma	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/25 14:35
S153	34	((before same (substrate or wafer)) same lift\$4)with plasma	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/25 14:37
S154	21	((before same (substrate or wafer)) with lift\$4)with plasma	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/25 15:39
S155	2	"20060011224"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/25 15:41
S156	13	"682054"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/25 15:41
S157	21	"623445"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/26 18:00
S158	5753	(plasma antenna with coil)with switch	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/26 18:44
S159	2137	(plasma antenna with coil)with switch and coil	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/26 18:43
S160	205957	((("118") or ("156") or ("343"))).CLAS.	USPAT; USOCR	OR	OFF	2007/10/26 18:43
S161	11	((plasma and antenna and coil) and switch). clm.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/26 18:44
S162	2	"20030003768"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/26 21:39

S163	700	"4951601"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/26 22:43
S164	13	(plasma near (deposit or process)) and (lift with (while or during) with (wafer or substrate) with plasma)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/26 23:00
S165	33	(plasma near (deposit or process)) and ((de near chuck)or (de-chuck) or (de near clamp)with (before or after) with (wafer or substrate) with plasma)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/26 23:15
S166	33	(plasma near (deposit or process)) and ((de near chuck)or (de-chuck) or (de near clamp)with (before) with (wafer or substrate) with plasma)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/26 23:15
S167	33	(plasma near (deposit or process)) and ((de near chuck)or (de-chuck) or (de near clamp)with (wafer or substrate)with (before near\$2 plasma))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/26 23:22
S168	9	(plasma near (deposit or process)) and (turn near off) with (RF or voltage or power) with (substarte or wafer)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/26 23:26
S169	35	"478315"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/27 00:14
S170	75	((de near chuck) or (de near clamp)) and plasma	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/27 00:15
S171	75	((de near chuck) or (de near clamp)) and plasma	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/27 00:15
S172	1	((de near chuck) or (de near clamp)) and (plasma near deposit)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/27 00:15

S173	33	((de near chuck) or (de near clamp)) and (plasma and deposit)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/27 00:16
S174	57341	((((de near chuck) or (de near clamp))with before or after) and (plasma and deposit)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/27 00:16
S175	4	((((de near chuck) or (de near clamp))with (before or after)) and (plasma and deposit)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/27 00:18
S176	0	((de near chuck) or (de near clamp))with (turn near off)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/27 00:43
S177	1	(plasma with deposit) and ((DC near voltage) with bias with (electrostatic near chuck))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/27 00:47
S178	72	"6316167"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/10/27 00:47
S179	56	trouiller.in.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/06/04 12:53
S180	1	S179 and plasma	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/06/04 12:54
S181	19	S179 and resist\$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/06/04 12:54
S182	48	yorick.in.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/06/04 12:57

S183	6	S179 and S182	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/06/04 12:58
S184	2	10/702049	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/06/04 13:01
S185	2	10/847891	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/06/04 13:03
S186	2	10/750348	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/06/04 13:07
S187	8	"6713386"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/06/04 13:08
S188	81	"6316167"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/06/04 13:54
S189	4	11/112880	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/06/04 15:44
S190	2	"20030216009"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/06/04 15:53
S191	214	((SiOC or SiON or ARC or TERA)with (Oxygen near plasma)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/06/04 21:43
S192	58	((SiOC or SiON or ARC or TERA)with (Oxygen near plasma))and (flow\$4 near rate)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/06/04 21:44

S193	43	((SiOC or SiON or ARC or TERA)with (Oxygen near plasma))and (oxygen with (scm or(flow\$4 near rate)))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/06/04 21:45
S194	83	"6316167"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/12/17 18:24
S195	2	10/702049	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/12/17 18:28
S196	12	RCHX and (hydrogen or water) and plasma	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/12/17 19:24
S197	8	RCHX and (hydrogen or water) and plasma and scm	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/12/17 19:27
S198	2	10/702049	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/12/17 19:27
S199	84	"6316167"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/12/18 15:38
S200	236607	(SiON or SiOC)withrate	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/12/18 17:14
S201	4478	(SiON or SiOC)with rate	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/12/18 17:14
S202	201	(SiON or SiOC)with rate with min	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/12/18 17:14

S203	1	(SON or SIOC)with rate with min with sec	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/12/18 17:14
S204	90	(SON or SIOC)with rate with min and ((SIOC or SION)with second)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/12/18 17:15
S205	17	(SON or SIOC)with MHZ	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/12/18 17:16
S206	1	(SON or SIOC)with MHZ and watt	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/12/18 17:16
S207	79	(SON or SIOC)and MHZ and watt	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/12/18 17:18
S208	52	(SON or SIOC)and MHZ and watt and RF	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/12/18 17:18
S209	2	10/702049	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/12/18 17:37
S210	34	(SON or SIOC)with(deposit\$4 near rate)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/12/18 17:47
S211	12	(SON or SIOC)with(deposit\$4 near rate with min)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/12/18 17:47
S212	34	(SON or SIOC)with(deposit\$4 near rate)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/12/18 17:49

S213	11	(SIOC)with(methane or "CH.sub.4" or "C.sub.2.H.sub.4" or "C.sub.2.H.sub.2" or "C.sub.6.H.sub.6")	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/12/18 18:40
S214	16	(RCHX)with(water or hydrogen or "H.sub.2" or "H.sub.2.O")	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/12/18 18:52
S215	4	(RCHX)and((water or hydrogen or "H.sub.2" or "H.sub.2.O")with rate)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/12/18 18:59
S216	6	(RCHX)and((water or hydrogen or "H.sub.2" or "H.sub.2.O")with rate)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/12/18 19:00
S217	87	(sicoh)and((water or hydrogen or "H.sub.2" or "H.sub.2.O")with rate)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/12/18 19:02
S218	12	(sicoh)same((water or hydrogen or "H.sub.2" or "H.sub.2.O")with rate)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/12/18 19:02
S219	2	"7332426"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/12/18 19:11
S220	7	"7030468"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/12/18 19:13
S221	2	10/702049	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/12/18 19:15
S222	525	(sicoh)same(water or hydrogen or "H.sub.2O" or "H.sub.2")	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/12/18 19:21

S223	12	(sicoh)same((water or hydrogen or "H.sub.2O" or "H.sub.2")with rate)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/12/18 19:22
S224	384	(sicoh)with((water or hydrogen or "H.sub.2O" or "H.sub.2"))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/12/18 19:28
S225	22	(sicoh)with((water or hydrogen or "H.sub.2O" or "H.sub.2")with gas)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/12/18 19:29
S226	0	"20020163028"	USPAT	OR	OFF	2009/06/18 17:29
S227	2	"20020163028"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2009/06/18 17:30
S228	2	"20020163028"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/18 17:30
S229	1	"6953609"	USPAT	OR	OFF	2009/06/18 17:46
S230	0	10/702049	USPAT	OR	OFF	2009/06/18 18:12
S231	2	10/702049	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2009/06/18 18:12
S232	1	11/145197	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2009/06/18 19:14
S233	271	plasma with (carbon near oxide or "CO.sub.2")with (helium or He)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2009/06/19 12:15
S234	281	plasma with (carbon near oxide or "CO.sub.2")with (helium or He)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/19 12:17

S235	43	plasma with (carbon near oxide or "CO. sub.2")with (helium or He)and(3MS or trimethyl near silane or trimethylsilane)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/19 12:18
S236	273	shower near head and plasma and (shower near head or showerhead)with center\$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/19 12:24
S237	802	chamber with pressure and plasma and 3ms and torr	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/19 12:55
S238	820	chamber with pressure and plasma and (trimethyl near silane or 3ms) and pressure with torr	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/19 12:55
S239	761	chamber with pressure and plasma and (trimethyl near silane or 3ms) and pressure with torr and deposit\$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/19 12:56
S240	221	chamber with pressure with plasma and (trimethyl near silane or 3ms) and pressure with torr and deposit\$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/19 12:56
S241	56	chamber with pressure with plasma and (trimethyl near silane or 3ms) and pressure with torr and deposit\$4 and (anti near reflect\$4 or ARC or TERA)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/19 12:57
S242	943	plasma with chamber and purg\$4 and (ARC or TERA or anti near reflect\$4)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/19 14:02
S243	943	plasma with chamber and purg\$4 and (ARC or TERA or anti near reflect\$4)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/19 14:02
S244	253	plasma with chamber and purg\$4 and (ARC or TERA or anti near reflect\$4)and(3MS or trimethyl silane)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/19 14:02

S245	40	plasma with chamber and purg\$4 and (ARC or TERA or anti near reflect\$4)and(3MS or trimethyl near silane)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/19 14:03
S246	31	plasma with chamber and purg\$4 and (ARC or TERA or anti near reflect\$4)and(3MS or trimethyl near silane)and (helium or He)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/19 14:04
S247	10	plasma with chamber and purg\$4 and (ARC or TERA or anti near reflect\$4)and(3MS or trimethyl near silane)and purg\$4 with (helium or He)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/19 14:04
S248	18	plasma with chamber and purg\$4 and (ARC or TERA or anti near reflect\$4)and(3MS or trimethyl near silane)and purg\$4 and (helium or He)with sccm	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/19 14:06
S249	20	plasma and shower near head with center with edge	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/19 14:12
S250	867	(3ms or trimethyl near silane).clm.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/19 15:13
S251	209	S250 and plasma	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/19 15:13
S252	4765	S250 and plasma and (RF and electrode)".clm"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/19 15:14
S253	94472	(RF and electrode)".clm"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/19 15:14
S254	77676	(RF and electrode)".clm"	US-PGPUB; USPAT	OR	ON	2009/06/19 15:14
S255	867	(3ms or trimethyl near silane).clm.	US-PGPUB; USPAT	OR	ON	2009/06/19 15:14
S256	36	S254 and S255	US-PGPUB; USPAT	OR	ON	2009/06/19 15:15

7/ 20/ 2009 3:43:32 PM

C:\ Documents and Settings\ ttadayyoneslami\ My Documents\ EAST\ Workspaces\ 10702049.wsp